CLAIMS

1. A sputtering target containing Ru as a main component, wherein the sputtering target ~~has a melting point higher than that of B_2O_3 and comprises a composite oxide containing boron~~comprises a composite oxide containing boron with a melting point higher than that of B_2O_3, and
wherein the composite oxide is one or more selected from the group consisting of $Co_2B_2O_5$, $CrBO_3$, $TiBO_3$ and $Mn_3B_2O_6$.

2. The sputtering target according to claim 1, wherein the sputtering target has a B content of 0.01 wt% or more.

3. The sputtering target according to claim 1 or 2, wherein the sputtering target has a relative density of 90% or more.

4. The sputtering target according to any one of claims 1 to 3, further comprising one or more selected from Co, Cr, Mn, and Ti as constituent elements, in addition to Ru, B, and O.

5. The sputtering target according to any one of claims 1 to 4, wherein the composite oxide has a melting point of 750 °C or more.

~~6. The sputtering target according to any one of claims 1 to 5, wherein the composite oxide is one or more selected from the group consisting of $Co_2B_2O_5$, $CrBO_3$, $TiBO_3$ and $Mn_3B_2O_6$.~~

~~7. (Cancel) A powder of a composite oxide for use in production of a sputtering target, wherein the composite oxide is a composite oxide having a melting point higher than that of B2O3, the composite oxide containing boron.~~

~~8. (Cancel) The powder according to claim 7, wherein the composite oxide has a melting point of 750 °C or more.~~

~~9. (Cancel) The powder according to claim 7 or 8, wherein the composite oxide is one or more selected from the group consisting of $Co_2B_2O_5$, $CrBO_3$, $TiBO_3$ and $Mn_3B_2O_6$.~~

~~10. (Cancel) The powder according to any one of claims 7 to 9, wherein the powder has a specific surface area of from 0.5 to 80 m^2/g, a particle size of from 0.3 to 15 μm, and/or an impurity concentration of 10000 wtppm or less.~~

~~11~~6.~~(New)~~ A method for manufacturing a sputtering target containing Ru as a main component, the method comprising:

mixing the Ru and a composite oxide having a melting point higher than that of B_2O_3 and containing boron, wherein the composite oxide is one or more selected from the group consisting of $Co_2B_2O_5$, $CrBO_3$, $TiBO_3$ and $Mn_3B_2O_6$.

~~12~~7.~~(New)~~ The method according to claim ~~11~~6, wherein the sputtering target has a B content of 0.01 wt% or more.

~~13~~8.~~(New)~~ The method according to claim ~~11~~ 6 or ~~12~~7, wherein the sputtering target has a relative density of 90% or more.

~~14~~9.~~(New)~~ The method according to any one of claims ~~11~~ 6 to ~~13~~8, wherein the sputtering target further comprises one or more selected from Co, Cr, Mn, and Ti as constituent elements, in addition to Ru, B, and O.

~~15~~10.~~(New)~~ The method according to any one of claims ~~11~~ 6 to ~~14~~9, wherein the composite oxide has a melting point of 750 °C or more.

~~16.(New) The method according to any one of claims 11 to 15, wherein the composite oxide is one or more selected from the group consisting of $Co_2B_2O_5$, $CrBO_3$, $TiBO_3$ and $Mn_3B_2O_6$.~~